

PHYSICS REQUIREMENT DOCUMENT (PRD)	Doc. No. SP-391-000-18 R0	LUSI SUB-SYSTEM XPP
Physics Requirements for the XPP Laser System		
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1. Overview

A short pulse laser system will be used to either stimulate a response in a sample or to probe the response of a sample after exposure to the LCLS beam. This system is a core component to the X-ray Pump-probe instrument. The system properties will ultimately define the scientific scope performed at this endstation and thus a configurable system is envisioned. This document describes the requirements of this system.

2. Performance Specifications

- 2.1.** Synchronization and Parameter Control Requirements
 - 2.1.1.** The repetition rate of the laser system shall be phase locked to the LCLS RF with less than 100 fs rms jitter for a frequency range between 0.00001 Hz and 10 kHz for all laser configurations.
 - 2.1.2.** The laser pulse shall be delivered to the sample with a spatial drift, both long and short term, less than 10% of the laser spot size for all configurations.
 - 2.1.3.** The following laser parameters shall be remotely controlled via the instrument controls system:
 - 2.1.3.1. Pointing on the sample
 - 2.1.3.2. Polarization state at the sample
 - 2.1.3.3. Pulse energy at the sample
 - 2.1.3.4. Pulse duration (up to 5 ps FWHM) and temporal shape (to the extent possible with a standard pulse shaping system)
 - 2.1.3.5. Arrival time with respect to the FEL pulse to any arbitrary time delay with a 10 fs precision neglecting jitter.
 - 2.1.3.6. Laser repetition rate (gating of the pulse train shall be accommodated)

- 2.2.** Medium Energy Ti:Sapphire Amplifier
 - 2.2.1.** Repetition Rate \geq 240 Hz
 - 2.2.2.** Pulse Energy $>$ 2 mJ at the sample
 $<$ 0.75% rms noise over 8 hours
 - 2.2.3.** Pulse duration $<$ 50 fs at the sample
 - 2.2.4.** $M^2 \leq 1.35$ at the OPA
 - 2.2.5.** Pre-pulse contrast ratio $> 10^5:1$
 - 2.2.6.** Post-pulse contrast ratio $> 10^3:1$
 - 2.2.7.** ASE contrast ratio $> 10^3:1$ [(Total Energy-ASE Energy)/ASE Energy]
- 2.3.** High Energy Ti:Sapphire Amplifier
 - 2.3.1.** Repetition Rate \geq 120 Hz
 - 2.3.2.** Pulse Energy $>$ 20 mJ at the sample,
 $<$ 1.5% rms fluctuations over 8 hours
 - 2.3.3.** Pulse duration $<$ 50 fs at the sample
 - 2.3.4.** $M^2 \leq 1.5$
 - 2.3.5.** Pre-pulse contrast ratio $> 10^5:1$
 - 2.3.6.** Post-pulse contrast ratio $> 10^3:1$
 - 2.3.7.** ASE contrast ratio $> 10^3:1$ [(Total Energy-ASE Energy)/ASE Energy]
- 2.4.** OPA
 - 2.4.1.** Tuning range from 0.25 μm to 20 μm
 - 2.4.2.** Pulse Energy $>$ 10 μJ at the sample over entire tuning range
 $>$ 100 μJ at the sample for 0.475 μm to 2.6 μm
 - 2.4.3.** Pulse duration $<$ 100 fs at the sample for all wavelengths
- 2.5.** Second Harmonic Generation System
 - 2.5.1.** $>$ 25% conversion efficiency for fundamental pulse energies $\geq 1 \text{ mJ}$
 - 2.5.2.** Pulse duration $<$ 100 fs
- 2.6.** Third Harmonic Generation System
 - 2.6.1.** $>$ 5% conversion efficiency for fundamental pulse energies $\geq 1 \text{ mJ}$
 - 2.6.2.** Pulse duration $<$ 100 fs

3. Diagnostics

The following laser properties shall be remotely monitored with diagnostics that are fully integrated into the instrument control and data system:

- 3.1.** Pulse energy (120 Hz)
 - 3.1.1.** Recorded in XPP experimental data files
 - 3.1.2.** 5% absolute accuracy
 - 3.1.3.** 1% relative accuracy
- 3.2.** Spatial profile (10 Hz)
- 3.3.** Pulse duration (10 Hz)
- 3.4.** Spectrum (10 Hz)
- 3.5.** Contrast ratio for 800 nm amplifiers (on demand - not continuously monitored)